

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-5 (Canceled).

Claim 6 (Currently Amended): ~~[[The]]~~ A pattern inspection method according to claim 1, comprising:

comparing a real pattern window having real pattern data corresponding to predetermined pixels of the real pattern data obtained by imaging an inspection object to a design pattern window corresponding to the real pattern window and shifted design pattern windows which are obtained by shifting the design pattern windows in a plurality of directions, respectively, wherein a shift width of the shifted design pattern windows is within one pixel;

selecting one window from the design pattern window and shifted design pattern windows;

comparing a center pixel of the real pattern window to a center pixel of the selected design pattern window; and

performing a pattern inspection of the inspection object, corresponding to the center pixel, according to a result of the comparison;

wherein the performing ~~step~~ comprises:

obtaining a difference value by subtracting a noticed pixel of the selected one window and predetermined pixels surrounding the noticed pixel of the selected one window from a noticed pixel of the real pattern window and predetermined pixels surrounding the noticed pixel of the real pattern window,

outputting 1) a "0" difference value in a case where the obtained difference value is within a difference value obtained by shifting the design pattern window by one pixel or less,

2) a difference value obtained by subtracting the minimum value from the obtained difference value in a case where the obtained difference value is less than a minimum value of difference values obtained by shifting the design pattern window and 3) a difference value obtained by subtracting a maximum value of difference values which are obtained by shifting the design pattern window by one pixel or less from the obtained difference value in a case where the obtained difference value is larger than the maximum value, and

performing the pattern inspection of the inspection object by comparing the outputted difference value with a threshold value set in advance.

Claim 7 (Previously Presented): The pattern inspection method according to claim 6, wherein the difference value is determined based on a lightness of pixels in the real pattern data and a lightness of pixels in design pattern data of the selected design pattern window.

Claims 8-12 (Canceled).

Claim 13 (Currently Amended): ~~[[The]]~~ A pattern inspection device according to claim 8, comprising:

means for comparing a real pattern window having real pattern data corresponding to predetermined pixels of the real pattern data obtained by imaging an inspection object to a design pattern window corresponding to the real pattern window and shifted design pattern windows which are obtained by shifting the design pattern windows in a plurality of directions, respectively, wherein a shift width of the shifted design pattern windows is within one pixel;

means for selecting one window from the design pattern window and shifted design pattern windows;

means for comparing a center pixel of the real pattern window to a center pixel of the selected design pattern window; and

means for performing a pattern inspection of the inspection object, corresponding to the center pixel, according to a result of the comparison;

wherein the means for performing comprises

obtaining a difference value by subtracting a noticed pixel of the selected one window and predetermined pixels surrounding the noticed pixel of the selected one window from a noticed pixel of the real pattern window and predetermined pixels surrounding the noticed pixel of the real pattern window,

outputting 1) a "0" difference value in a case where the obtained difference value is within a difference value obtained by shifting the design pattern window by one pixel or less, 2) a difference value obtained by subtracting the minimum value from the obtained difference value in a case where the obtained difference value is less than a minimum value of difference values obtained by shifting the design pattern window and 3) a difference value obtained by subtracting a maximum value of difference values which are obtained by shifting the design pattern window by one pixel or less from the obtained difference value in a case where the obtained difference value is larger than the maximum value, and

performing the pattern inspection of the inspection object by comparing the outputted difference value with a threshold value set in advance.

Claim 14 (Previously Presented): The pattern inspection device according to claim

13,

wherein the difference value is determined based on a lightness of pixels in the real pattern data and a lightness of pixels in design pattern data of the selected design pattern window.

Claims 15-19 (Canceled).

Claim 20 (Currently Amended): ~~[[The]]~~ A method according to claim 15, of manufacturing a mask comprising:

preparing a substrate with a light shielding film on which a mask pattern is formed;
and

inspecting the substrate with the light shielding film on which a mask pattern is formed, wherein the inspecting comprises:

comparing a real pattern window having real pattern data corresponding to predetermined pixels of the real pattern data obtained by imaging the mask pattern to a design pattern window corresponding to the real pattern window and shifted design pattern windows which are obtained by shifting the design pattern windows in a plurality of directions respectively, wherein a shift width of the shifted design pattern windows is within one pixel;

selecting one window from the design pattern window and shifted design pattern windows;

comparing a center pixel of the real pattern window to a center pixel of the selected design pattern window; and

performing a pattern inspection of the mask pattern corresponding to the center pixel according to a result of the comparison;

wherein the performing ~~step~~ comprises:

obtaining a difference value by subtracting a noticed pixel of the selected one window and predetermined pixels surrounding the noticed pixel of the selected one window from a noticed pixel of the real pattern window and predetermined pixels surrounding the noticed pixel of the real pattern window,

outputting 1) a "0" difference value in a case where the obtained difference value is within a. difference value obtained by shifting the design pattern window by one pixel or less, 2) a difference value obtained by subtracting the minimum value from the obtained difference value in a case where the obtained difference value is less than a minimum value of difference values obtained by shifting the design pattern window and 3) a difference value obtained by subtracting a maximum value of difference values which are obtained by shifting the design pattern window by one pixel or less from the obtained difference value in a case where the obtained difference value is larger than the maximum value, and

performing the pattern inspection of the mask pattern by comparing the outputted difference value with a threshold value set in advance.

Claims 21-31 (Canceled).